

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trudemark Office
Address: COMMISSIONER OF PATENTS AND TRADEMARKS
Washington, Dc. 20231
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/427,675	10/27/1999	ERIC JACQUINOT	JACQUINOT=7	3607	
1444	7590 09/25/2002				
BROWDY AND NEIMARK, P.L.L.C.			EXAMINER		
624 NINTH S SUITE 300			DEO, D		
WASHINGTON, DC 20001-5303			ART UNIT	PAPER NUMBER	
			1765		
			DATE MAILED: 09/25/2002	ATE MAILED: 09/25/2002	

Please find below and/or attached an Office communication concerning this application or proceeding.

<u></u>			4
	Application No.	Applicant(s)	
_	09/427,675	JACQUINOT ET AL.	
Office Action Summary	Examiner	Art Unit	
	DuyVu n Deo	1765	
The MAILING DATE of this communication a Period for Reply	appears on the cover sheet w	vith the correspondence address	
A SHORTENED STATUTORY PERIOD FOR REF THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a communication of the period for reply specified above, the maximum statutory perions for reply within the set or extended period for reply will, by station of the period for reply will, by station of the period for reply will, by station of the period for reply will. - Any reply received by the Office later than three months after the material patent term adjustment. See 37 CFR 1.704(b). - Status	N. t 1.136(a). In no event, however, may a reply within the statutory minimum of the iod will apply and will expire SIX (6) MC tute, cause the application to become a	reply be timely filed irty (30) days will be considered timely. NTHS from the mailing date of this communication. NBANDONED (35 U.S.C. § 133).	
1) Responsive to communication(s) filed on 1	2 August 2002 .		
2a) ☐ This action is FINAL . 2b) ☑	This action is non-final.		
Since this application is in condition for allocation accordance with the practice und			i.
Disposition of Claims			
4) Claim(s) <u>17-39</u> is/are pending in the applica			
4a) Of the above claim(s) is/are withd	lrawn from consideration.		
5) Claim(s) is/are allowed.			
6)⊠ Claim(s) <u>17-39</u> is/are rejected.			
7) Claim(s) is/are objected to.			
8) Claim(s) are subject to restriction and Application Papers	d/or election requirement.		
9)☐ The specification is objected to by the Exami	ner.		
10) ☐ The drawing(s) filed on is/are: a) ☐ ac	cepted or b) objected to by	the Examiner.	
Applicant may not request that any objection to	<u> </u>		
11) The proposed drawing correction filed on		disapproved by the Examiner.	
If approved, corrected drawings are required in	• •		
12) The oath or declaration is objected to by the	Examiner.		
Priority under 35 U.S.C. §§ 119 and 120			
13) Acknowledgment is made of a claim for fore	ign priority under 35 U.S.C.	§ 119(a)-(d) or (f).	
a) ☐ All b) ☐ Some * c) ☐ None of:			
1. Certified copies of the priority docume			
2. Certified copies of the priority docume			
 3. Copies of the certified copies of the prapplication from the International I * See the attached detailed Office action for a limit 	Bureau (PCT Rule 17.2(a)).	•	
14) Acknowledgment is made of a claim for dome	stic priority under 35 U.S.C	§ 119(e) (to a provisional application	n).
a) ☐ The translation of the foreign language p 15)☐ Acknowledgment is made of a claim for dome			
Attachment(s)	•		
Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449) Paper No(s	5) Notice of	Summary (PTO-413) Paper No(s) Informal Patent Application (PTO-152)	

U.S. Patent and Trademark Office PTO-326 (Rev. 04-01)

Page 2

Application/Control Number: 09/427,675

Art Unit: 1765

DETAILED ACTION

Response to Arguments

1. Applicant's arguments with respect to claims 17-36 have been considered but are moot in view of the new ground(s) of rejection.

Claim Rejections - 35 USC § 112

- 2. The following is a quotation of the first paragraph of 35 U.S.C. 112:
 - The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.
- 3. Claim 37 is rejected under 35 U.S.C. 112, first paragraph, as containing subject matter which was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventor(s), at the time the application was filed, had possession of the claimed invention. Applicant has not described where in the specification teaching of the abrasive liquid composition consists essentially of an aqueous acid suspension of individualized colloidal silica particles not linked to each other by siloxane bonds and a surfactant.

Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 17-39 are rejected under 35 U.S.C. 103(a) as being unpatentable over Jacquinot et al. (US 6,043,159) and Grover et al. (US 5,759,917).

Application/Control Number: 09/427,675

Art Unit: 1765

Jacquinot teaches a polishing an integrated circuit in which isolation layer, including silicon oxide and silicon nitride, is polished by an abrasive composition which comprises an aqueous acid suspension of individualized colloidal silica particles not linked to each other by siloxane bonds. The pH of the composition is about 1.5-4, the abrasives have diameters about 10-50 nm and a concentration of about 15-30% (col. 2, line 39-65; col. 4, line 1-10). Unlike claimed invention he doesn't describe that the support is impregnated with an abrasive liquid composition. However, since the polishing pad is soaked with the abrasive liquid composition during the polishing, the abrasive liquid composition would get into the abrasive pad and therefore, this would create claimed polishing pad that impregnated with an abrasive composition.

Unlike claimed invention, Jacquinot doesn't describe having a surfactant in the abrasive composition. Grover teaches a method of polishing the oxide layer using a surfactant in the abrasive composition. The surfactant can be anionic or nonionic (col. 6, line 38-48). It would have been obvious for one skill in the art at the time of the invention in light of Grover to add a surfactant because Grover teaches that a surfactant is used to improve the within-wafer-non-uniformity (WIWNU) of the wafers, thereby improving the surface of the wafer and reducing wafer defects (col. 6, line 45-48). The combined method would read on claimed the abrasive liquid composition consists essentially of an aqueous acid suspension of individualized colloidal silica particles not linked to each other by siloxane bonds and a surfactant.

Referring to claims 31-36, Grover teaches that the surfactant concentration should be at 0.001-10%, and he teaches that it will typically vary depending on the particular surfactant

Application/Control Number: 09/427,675

Art Unit: 1765

Page 4

selected and the nature of the surface of the metal oxide abrasive and the amount of additive is adjusted to achieve the desired concentration in the polishing slurry (col. 6, line 49-64).

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to DuyVu n Deo whose telephone number is 703-305-0515.

DVD

September 20, 2002

BENJAMIN L. UTECH SUPERVISORY PATENT EXAMINER

my do

TECHNOLOGY CENTER 1700